Gas-Phase Generation and Characterization of Methyl- and Dimethylsilylene and Their Cations by Collisional Activation and Neutralization-Reionization Mass Spectrometry

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Results of mass spectrometric measurements are reported which characterize the chemical bonding in the radical cations $(CH_3SiH)^{*+}$ and $(CH_3)_2Si^{*+}$ and provide evidence for the existence of the corresponding neutral silylene molecules CH_3SiH and $(CH_3)_2Si$ in the gas phase. The experiments were performed with a modified four-sector ZAB mass spectrometer with a BEBE configuration and collision cells mounted in the intermediate field-free regions B(1)/E(1), E(1)/B(2), and B(2)E(2). Observed collisional activation (CA) mass spectra of the ions $[H_4, C, Si]^+$ and $[H_6, C_2, Si]^+$ generated from electron impact of tetramethylsilane and other precursors and CA/CA spectra of the $[C, H_3, Si]^+$ derived from them are most compatible with the connectivities CH_3SiH^{*+} and $(CH_3)_2Si^{*+}$. Neutralization-reionization (NRMS) experiments and CA experiments with the "recovery" signals established identical connectivities for the corresponding neutral species.

Introduction

The growing interest in Si–C double-bonded molecules is exemplified by the continuing attention received by the molecules silaethylene ($H_2Si=CH_2$) and 1-methylsilaethylene ($CH_3(H)$ -Si= CH_2) and their silylene isomers methylsilylene ($HSiCH_3$) and dimethylsilylene ((CH_3)₂Si) from both experimentalists and theoreticians. Both of these molecules have been invoked as reactive intermediates in the gas phase, particularly in the thermal and photochemical decompositions of organosilicon compounds¹ and in the condensed phase.² Evidence for their existence has come from matrix isolation experiments.³ Dimethylsilylene has been observed in absorption in the gas phase, but methylsilylene has been more elusive.⁴

Very recently, ions with the elemental compositions $[C,H_4,-Si]^{*+}$ and $[C_2,H_6,Si]^{*+}$ have become of interest in gas-phase ion chemistry, particularly in the reactions of Si^{*+} with methane and ethane at room temperature and elevated energies.⁵⁻⁷ The formation of the adduct ion, Si^{*+}(C_2H_6), has been reported in two gas-phase experimental investigations of the reaction of Si^{*+} with ethane.^{6,7} Observations of other products and mechanistic arguments favor a structure for this adduct and for the intermediate complex leading to bimolecular products corresponding to ionized dimethylsilylene which may be formed by C-C bond insertion.

Theory has been applied to investigate the absolute and relative stabilities of methyl- and dimethylsilylene, for both the neutrals and their cations. There is agreement between theory and experiment on the relative stability of the neutral isomers. Gasphase experiments with ion cyclotron double-resonance spectroscopy⁸ on the thresholds for deprotonation of the protonated species have established a higher stability for the silaethylene than methylsilylene by 10 ± 3 kcal mol⁻¹, but the difference obtained by the latest theory is somewhat smaller.⁹ A third isomer, silylmethylene (H₃SiCH), has been predicted by theory to lie 65.5 kcal mol⁻¹ above silaethylene on the singlet surface with a very small barrier (<3 kcal mol⁻¹) to its rearrangement to H₂-Si=CH₂ (¹A₁).¹⁰ The barrier to the rearrangement of singlet methylsilylene to singlet silaethylene has been estimated to be about 40 kcal mol⁻¹. One previous report on computed energies of the positive ions of methylsilylene and silaethylene predicts that HSiCH₃^{•+} lies 6.7 kcal mol⁻¹ below the energy of H₂SiCH₂^{•+} and a barrier of 42.6 kcal mol⁻¹ for the interconversion of HSiCH₃^{•+} to H₂SiCH₂^{•+.6}

The dimethylsilylene molecule, $(CH_3)_2Si$; is often invoked as a reactive intermediate and has been studied extensively in the condensed phase.² It was first prepared and spectroscopically identified in hydrocarbon glasses and inert gas matrices at low temperatures in 1979.¹¹ Since then, this molecule has been subjected to IR, UV, and fluorescence studies in inert matrices^{11,12} and in solution.¹³ The interpretation of the UV spectrum, in particular, has been somewhat controversial.¹⁴ An early theoretical study by Gordon and co-workers addressed the relative stabilities of six isomers of dimethylsilylene.¹⁵

The relative stability of dimethylsilylene and 1-methylsilaethylene has received much attention, but here again the results are somewhat controversial. Early matrix-isolation experiments. which showed that at 10 K dimethylsilylene rapidly converts upon photochemical excitation to 1-methylsilaethylene but reverts at elevated temperatures (100-120 K), suggested that the silylene is more stable and that the barrier to interconversion is small. <5kcal mol^{-1,12} However, later ICR experiments provided enthalpies of formation of 18 and 46 kcal mol⁻¹ for the silaethylene and silvlene isomers, respectively, and so indicated an energy difference of 28 kcal mol⁻¹ in favor of the silaolefin.¹⁶ Calculations also predicted a sizable barrier, 40.6 kcal mol⁻¹, for the oligomerization.¹⁷ Walsh has derived an enthalpy of formation for the silvlene of 26 kcal mol⁻¹ on the basis of thermochemical arguments.¹⁸ but this is 20 kcal mol⁻¹ lower than the ICR result. The possibility has been raised that this difference is due to the singlet-triplet splitting which has been calculated to be 22.1 kcal mol⁻¹, with the singlet more stable.¹⁹

In this study the dimethylsilylene cation, $Si(CH_3)_2^{*+}$, is generated directly by electron impact of a molecule which contains its template, e.g., tetramethylsilane. The cation is then interrogated by collisional activation $(CA)^{20}$ to deduce its connectivity and by neutralization-reionization $(NR)^{21}$ mass spectrometry to generate the corresponding neutral dimethylsilylene molecule Si- $(CH_3)_2$ and interrogate its structural features. Similar investigations are performed with $HSiCH_3^{*+}$. CA and NR mass spectrometry together have been shown to provide a powerful method for the interrogation of structural properties of closely related ions and molecules in the gas phase,²² particularly if they

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Figure 1. CA mass spectrum (He, 80% T) of m/z 44 [H4,C,Si]⁺⁺ generated from Si(CH₃)₄ by electron impact. The insert shows the MI spectrum of m/z 44.

are inherently reactive so that they cannot easily be isolated and investigated with other techniques.

Experimental Section

The experiments were performed with a substantially-modified ZAB-HF mass spectrometer (V.G. Analytical Ltd., Wythenshawe, Manchester M23 9LE, U.K.) which has been described in detail previously.²³ The facility is a four-sector mass spectrometer with BEBE configuration. Positive ions [H4,C,Si]+ were generated by the ionization of tetramethylsilane and methylchlorosilane with 70-eV electrons, while $[H_6, C_2, Si]^+$ were similarly generated from tetramethylsilane, trimethylsilyl chloride, trimethylsilylacetylene, (CH₃)₃SiC₂H, and 1,1-dimethylsilacyclobutane, $c-(CH_2)_3Si(CH_3)_2$. The ion source conditions were as follows: ion trap current = 100 μ A; ion source temperature = 200 °C; mass resolution $m/\Delta m = 1500$ (10% valley definition).

Collisional activation²⁰ used to characterize the ions leaving the source was achieved by mass-selecting the 8-keV ion beam by means of B(1)E(1) and colliding it, in the case of the positive ions, in a collision chamber located in the third field-free region (He, 80% transmittance, T). Ionic products were recorded by scanning B(2). In the NRMS experiments,²¹ the 8-keV beam of positive ions was neutralized with xenon (70% T) in the first cell of a differentially-pumped tandem-collision cell located in the field-free region between E(1) and B(2). Unreacted ions were deflected away from the beam of neutral species by applying a voltage of 1000 V on the deflector electrode. Subsequent reionization occurred in the second collision cell by collision with oxygen (70% T). The resulting mass spectra were recorded by scanning B(2). The minimum lifetime t (equal to the transit time from the first to the second cell) is of the order of a microsecond.

In all experiments signal-averaging techniques were used to improve the S/N ratio. The data were accumulated by on-line processes using an AMD-Intectra computer system DP10.

Results and Discussion

Methylsilylene. The CA mass spectrum of the ion at m/z 44 with the elemental composition [H₄,C,Si]⁺ derived from tetramethylsilane by electron impact is shown in Figure 1. By far the most dominant feature in the spectrum is the strong peak at m/z 43, $[H_3,C,Si]^+$, corresponding to the loss of H[•]. The preference of H. loss is very suggestive of the connectivity H-SiCH₃ or H-CSiH₃ rather than H₂CSiH₂ and so is consistent with theory which predicts a large barrier (42.6 kcal mol^{-1}) for the interconversion of HSiCH₃⁺⁺ to H₂SiCH₂^{++,6} Peaks corresponding to the loss of up to all four hydrogen atoms are also easily identified, and there is no special intensity associated with



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Figure 2. NR mass spectrum (Xe, 70% T; O₂, 70% T) of [H₄,C,Si]*+. The total contribution of the isotopic peaks to the recovery signal at m/z44 is 6.4%. The insert shows the NRMS/CA of m/z 44 (He II O₂, 70%) T).

the peak corresponding to loss of H_2 . The significant signal for SiH⁺ corresponds to loss of CH₃⁺ and so is a signature of the connectivity HSi-CH₃ rather than HC-SiH₃. There is no evidence for a signal at CH⁺ to indicate the connectivity HC-SiH₃. The relatively strong Si⁺⁺ peak corresponds to loss of both H. and CH3. and so is consistent with the connectivity H-Si-CH₃. The observed metastable ion decomposition of m/z 44 (see insert, Figure 1) again shows the combined loss of CH3 '/H' which in this case predominates over loss of H[•]. Taken together, the spectral data obtained for the ion [H₄,C,Si]⁺ derived from tetramethylsilane by electron impact are most compatible with the connectivity H-Si-CH₃, i.e., the existence of the radical cation HSiCH₃·+.

Figure 2 shows the mass spectrum which is observed when the m/z 44 ion is neutralized and reionized in a NRMS-type experiment. The observation of the intense recovery signal implies the occurrence of nearly vertical neutralization and reionization processes and thus a retention of the connectivity and geometry of the initial m/z 44 ion, HSiCH₃⁺. The remainder of the spectrum is generally supportive of this conclusion in that it contains the same diagnostic peaks observed in the CA spectrum of the initial m/z 44 ion shown in Figure 1. It also includes a signature of the CH₃ linkage in the form of the C⁺⁺, CH⁺, CH₂⁺⁺, and CH_3^+ distribution. The trace peak at m/z 16 corresponds to CH4*+ and thus the loss of Si by reductive elimination. Apparently, the intermediate HSiCH₃ neutral does not isomerize to $H_2Si=CH_2$ or H_3SiCH . This is consistent with the barrier of 40 kcal mol⁻¹ predicted by theory for the interconversion of singlet methylsilylene to singlet silaethylene and the high energy of silvlmethylene, which is predicted by theory to lie 65.5 kcal mol⁻¹ above silaethylene.¹⁰

Dimethylsilylene. The observed metastable ion decompositions of $(CH_3)_4Si^{++}$ (m/z 88) indicate both the direct and sequential loss of two methyl groups to produce m/z 58. These results suggest that the connectivity H₃C-Si-CH₃, present in the tetramethylsilane molecule chosen as parent is preserved in the daughter ion at m/z 58 produced by electron impact ionization at 70 eV.

The CA mass spectrum of the ion at m/z 58 with the elemental composition $[H_6, C_2, Si]^+$ derived from tetramethylsilane by electron impact is shown in Figure 3. By far, the most dominant feature in the spectrum is the strong peak at m/z 43 [H₃,C,Si]⁺, corresponding to the loss of CH₃. Peaks corresponding to the loss of up to six hydrogen atoms are easily identified with the peak corresponding to the loss of two H (H₂) at m/z 56 being the most intense. Weak fragment ion signals are observed at m/z 42 [H₂,C,Si]⁺ and 41 [H,C,Si]⁺. Still weaker signals are evident in the CA spectrum at m/z 29 [SiH⁺ or C₂H₅⁺], 28 [Si⁺⁺



Figure 3. CA mass spectrum (He, 80% T) of m/z 58 [H₆,C₂,Si]⁺⁺ generated from Si(CH₃)₄ by electron impact. The insert shows the MI spectrum of m/z 58.



Figure 4. CA/CA mass spectrum of m/z 43 generated from m/z 58 (He, 80% T; He, 80% T). The insert shows reference CA of m/z 43 generated in the source from tetramethylsilane.

or $C_2H_4^{*+}$], and 30 [SiH₂^{*+} or $C_2H_3^{+}$]. The metastable ion mass spectrum (insert in Figure 3) of m/z 58 indicates that the energetically most favored channels are due to dehydrogenation (to form SiC₂H₄^{*+}) and loss of a methyl radical (to form SiCH₃⁺).

In analyzing the CA mass spectrum shown in Figure 3, we may note first that the strong peak at m/z 43 requires the connectivity SiC and arises from the loss of $[C,H_3]$, most likely bound as a methyl group. (Loss of more than one fragment, e.g., $H^{\bullet} + CH_2$ where H^{\bullet} might be bound initially on the Si, should be less likely to lead to such a predominant signal at m/z 43.) There is little direct evidence for a C-C connectivity because ions at $C_2H_x^+$ (x = 0-6) at m/z = 24-30 are essentially absent in the spectrum. The small peaks at m/z 28 and 29 also may be due to Si⁺⁺ and SiH⁺. As a consequence, the backbone CSiC rather than CCSi is indicated for the m/z 58 ion. Support for methyl group bonding of the hydrogen atoms comes from the CA/CA mass spectrum shown in Figure 4, which shows a strong peak at Si⁺⁺ which can arise from the direct loss of a methyl group and no corresponding C^{+} peak which might arise from the loss of a SiH₃[•] group. There is also some evidence for the production of CH_3^+ . The CA/CA mass spectrum is identical to the CA mass spectrum of [H₃,C,Si]⁺ derived by electron impact of tetramethylsilane (see insert in Figure 2). The bonding of three H[•] atoms on C rules out a cyclic structure having a CSiC backbone.

Figure 5 shows the mass spectrum which is observed when the m/z 58 ion is neutralized and reionized in a NRMS-type experiment. The observation of the recovery signal again implies the occurrence of nearly vertical neutralization and ionization processes and thus, in this case, a retention of the connectivity of the initial m/z 58 ion. The remainder of the spectrum is



Figure 5. NR mass spectrum (Xe, 70% T; O₂, 70% T) of $[H_6,C_2,Si]^{++}$. The insert shows the NRMS/CA of m/z 58 (He, 70% T).

generally supportive of this conclusion in that it contains the diagnostic peaks observed in the CA mass spectrum of the initial m/z 58 ion shown in Figure 3. It also includes a signature of the CH₃ linkage in the form of the C⁺⁺, CH⁺, CH₂⁺⁺, and CH₃⁺⁺ distribution. Further support for our assignment is provided by the interference-free CA mass spectrum of reionized [H₆,C₂,Si], the insert in Figure 5, which clearly establishes a signal due to loss of CH₃⁺ (to form SiCH₃⁺).

Conclusions

1. Collisional activation experiments have provided evidence for the radical cations $HSiCH_3^{*+}$ and $(CH_3)_2Si^{*+}$ arising from various silane derivatives by electron impact at 70 eV.

2. Neutralization-reionization experiments have provided evidence for the existence of the neutral species $HSiCH_3$ and $(CH_3)_2Si$ derived from their corresponding radical cations by neutralization at high collision energies of 8 keV.

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